

MICRO DEVICES MANUFACTURING METHOD
AND APPARATUS THEREFOR

ABSTRACT OF DISCLOSURE:

An exposure method according to the present invention
5 includes a first step of forming on a substrate an alignment
mark including a concave and convex pattern; a second
step of forming a coat over said alignment mark and the
other area on said substrate; a third step of flattening
said coat; and a fourth step of applying a photosensitive
10 material on said coat flattened by said third step and
projecting a mask pattern thereto. The alignment mark is
formed by said concave and convex pattern arranged with a
pitch which is smaller than the predetermined value between
adjacent convex portions having a width of not less than
15 a predetermined value.